

REMARKS

Restriction

As indicated above and by the Examiner, applicants respectfully confirm election for continued prosecution of claims 1-7 and 9-12. Applicants affirm withdrawal of claims 13-34 from further consideration as requested by the Examiner.

Rejection pursuant to 35 USC §112

The Examiner has rejected claims 6 and 7 as being indefinite. Namely, the Examiner notes that the claims are devoid of claim language. Pursuant to the Examiner's suggestion, claim language has been added for claiming of the indicated composition. Additionally, for clarification, the composition has been amended to replace the term 'thd' with '2,2,6,6-tetramethyl-3,5-heptanedionate'. Therefore, removal of the rejection is respectfully requested.

Rejections pursuant to 35 USC § 102

The Examiner has rejected independent claims 1, 11, and 12 as anticipated by Suzuki (U.S. Pat. No. 4,182,824) along with dependent claims 2-7. Namely, the Examiner states that Suzuki teaches silanes (or other "material limitations") "substantially" as claimed. As indicated below, this fails to give cause for a 102 rejection. Nevertheless, all independent claims have been amended and all remaining claims are now in condition for allowance.

Rejections falling under 35 USC § 102 require more than a teaching of *material limitations substantially as claimed* (emphasis added). Rather, a teaching of "the invention" is required.

Nevertheless, the Examiner does indicate that claims 8-10 are objected to for dependence upon a rejected base claim. In accordance therewith, claim 8 has been canceled with the limitation thereof to a 'solvent solution' inserted into independent claim 1.

Independent claims 12 and 13 are to particular silicon based formulas. The claims have been amended to clarify that the particular silicon based formula claimed is 'for use in chemical vapor deposition' (CVD). That is, not only does Suzuki fail to disclose the exact formula claimed, Suzuki also fails to make any mention of a silicon based formula for use in CVD applications.

The amendments to the independent claims as indicated above are sufficient to place all pending claims in condition for allowance. Therefore, removal of rejections pursuant to 35 USC § 102 is respectfully requested.

Conclusion

In light of the above remarks, applicants respectfully submit that claims 1-7 and 9-12 are in condition for allowance. The Examiner is requested to contact the undersigned attorney at (203) 794-1100 should this be seen as helpful in advancement of prosecution of this application.

VERSION OF CLAIMS WITH MARKINGS TO SHOW CHANGES MADE

1. (Amended) A solvent solution including a hexacoordinated silicon beta-diketonate composition of the formula $R_2Si(\beta\text{-diketonate})_2$ or $(RO)_2Si(\beta\text{-diketonate})_2$, wherein each R is the same as or different from the other R, and each R is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.
2. (Amended) The solvent solution[composition] of claim 1, wherein each β -diketonate ligand of the composition may be the same as or different from the other β -diketonate ligand of the composition, and is independently selected from: 2,2,6,6-tetramethyl-3,5-heptanedionate; 1,1,1,2,2,3,3-hepta-fluoro-7,7-dimethyloctane-4,6-dionate; acetylacetonate; trifluoroacetylacetonate; and hexafluoroacetylacetonate.
3. (Amended) The solvent solution[composition] of claim 1, wherein each β -diketonate ligand of the composition is 2,2,6,6-tetramethyl-3,5-heptanedionate.
4. (Amended) The solvent solution[composition] of claim 1, wherein the composition is of the formula $R_2Si(\beta\text{-diketonate})_2$.
5. (Amended) The solvent solution[composition] of claim 1, wherein the composition is of the formula $(RO)_2Si(\beta\text{-diketonate})_2$.
6. (Amended) The solvent solution of claim 1, wherein the composition is of the formula $(t\text{-BuO})_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2[(t\text{-BuO})_2Si(thd)_2]$.

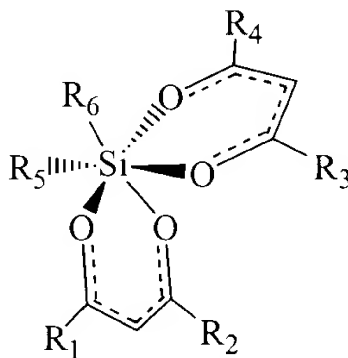
7. (Amended) The solvent solution of claim 1, wherein the composition is of the formula $(\text{CH}_3)_2\text{Si}(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2[(\text{CH}_3)_2\text{Si}(\text{thd})_2]$.

8. (Canceled)

9. (Amended) The solvent solution [formulation] of claim 1[8, wherein the liquid solvent solution includes] including a hydrocarbon solvent.

10. (Amended) The solvent solution of claim 1[formulation of claim 8, wherein the liquid solvent solution includes] including octane.

11. (Amended) A silicon β -diketonate for use in chemical vapor deposition and of the formula:

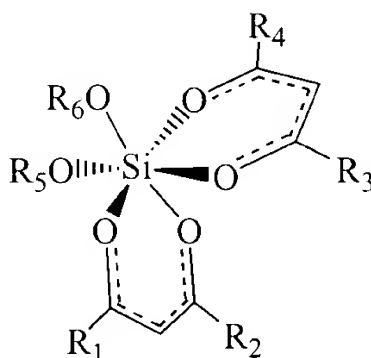


wherein:

R_1 , R_2 , R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl; and

R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

12. (Amended) A silicon β -diketonate for use in chemical vapor deposition and of the formula:



wherein:

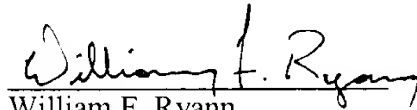
R_1 , R_2 , R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl and $C_1 - C_{12}$ silicon-containing alkyl; and

R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

13-34. (Canceled)

Please charge any deficiency or credit any overpayment to Deposit Account No. 50-0860.

Respectfully submitted,

A handwritten signature in cursive script, reading "William F. Ryann".

William F. Ryann
Registration No. 44,313

Advanced Technology Materials, Inc.
7 Commerce Dr.
Danbury, Ct. 06810
203 794-1100, Ext. 4140
203 797-2544 Fax
Attorney Ref: ATMI-353